

What is claimed is:

1. An apparatus for coating a substrate, the apparatus comprising:

5 a coating source for processing the substrate;

a sensor that generates a sensor signal at an output that is related to the actual status of the coating process; and

10 means for generating a control signal related to the sensor signal for modifying at least one operating parameter of the coating source during the processing of the substrate, wherein the sensor signal does not reflect the at least one operating parameter.

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2. A method for processing a substrate, the method comprising:

processing the substrate in a treatment area of a treatment source substantially according to a predetermined scheme comprising a set of parameters;

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selecting a subset of said set with at least one parameter as control parameter(s) and at least one further parameter not comprised in said subset as operating parameter(s);

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determining a deviation of the subset from the predetermined scheme;

generating a control signal in response to the determined deviation; and

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modifying the at least one operating parameter(s) in response to the control signal to compensate for an effect of the deviation from the predetermined scheme.

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